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Notice of Allowability 09	Application No.	Applicant(s)	
	09/761,489	ABDUL-RIDHA ET AL.	
	Examiner	Art Unit	
	Nguyen T Ha	2831	
The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R of the Office or upon petition by the applicant. See 37 CFR 1.31	S (OR REMAINS) CLOSED i ) or other appropriate comm RIGHTS. This application is	n this application. If not included unication will be mailed in due cours	se. THIS
1. $\boxtimes$ This communication is responsive to <u>8/24/2004</u> .			
2. ☑ The allowed claim(s) is/are <u>7-11 and 21-47</u> .			
3. $\boxtimes$ The drawings filed on <u>05 March 2001</u> are accepted by the	Examiner.		
<ul> <li>4. ☐ Acknowledgment is made of a claim for foreign priority u</li> <li>a) ☐ All b) ☐ Some* c) ☐ None of the:</li> <li>1. ☐ Certified copies of the priority documents hav</li> </ul>	e been received.		
2. Certified copies of the priority documents hav			
<ol> <li>Copies of the certified copies of the priority do International Bureau (PCT Rule 17.2(a)).</li> </ol>	ocuments have been receive	ed in this national stage application f	rom the
* Certified copies not received:			
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDON! THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		e a reply complying with the requirer	ments
5. A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which giv			E OF
6. CORRECTED DRAWINGS ( as "replacement sheets") mu	st be submitted.		
(a)  including changes required by the Notice of Draftsper	son's Patent Drawing Revie	w ( PTO-948) attached	
1) 🗌 hereto or 2) 🔲 to Paper No./Mail Date	<b>_</b> •		
(b) including changes required by the attached Examiner Paper No./Mail Date	's Amendment / Comment o	r in the Office action of	
Identifying indicia such as the application number (see 37 CFR each sheet. Replacement sheet(s) should be labeled as such in			t) of
7. DEPOSIT OF and/or INFORMATION about the depo attached Examiner's comment regarding REQUIREMENT	SSIT OF BIOLOGICAL MAT FOR THE DEPOSIT OF BI	ERIAL must be submitted. Note to OLOGICAL MATERIAL.	the
Attachment(s)			
1. Notice of References Cited (PTO-892)		nformal Patent Application (PTO-152	2)
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	Paper No.	Summary (PTO-413), /Mail Date	
<ol> <li>Information Disclosure Statements (PTO-1449 or PTO/SB/ Paper No./Mail Date</li> </ol>		Amendment/Comment	
4. Examiner's Comment Regarding Requirement for Deposit		Statement of Reasons for Allowand	Э
of Biological Material	9. 🗌 Other	•	

## **DETAILED ACTION**

1. The request filed on 8/24/2004 for a Request for Continued Examination (RCE) under 37 CFR 1.53(d) based on parent Application No. 09/761,489 is acceptable and a RCE has been established. An action on the RCE follows.

## Allowable Subject Matter

2. Claims 7-11 and 21-47 are allowed.

The following is an examiner's statement of reasons for allowance:

With respect to claims 7-11, the prior art alone or in combination does not teach the limitation of a structure comprising a first and second layer of metallic tantalum nitride, the first layer of metallic tantalum nitride being situated between a dielectric comprising ceramic tantalum nitride and a first capacitor electrode and the second layer of metallic tantalum nitride being situated between the dielectric comprising ceramic tantalum nitride and the second capacitor electrode.

With respect to claims 21-33, the prior art alone or in combination does not teach the limitations of the structure capacitor comprising a first barrier layer over the bottom copper interconnect metal segment, a copper seed layer over the first barrier layer, a dielectric comprising tantalum nitride over copper seed layer, and a second barrier layer over the dielectric.

With respect to claims 34-47, the prior art alone or in combination does not teach the limitation of the capacitor comprising a first barrier layer over the bottom interconnect metal segment, a seed layer over the first barrier layer, a dielectric over the seed layer, a second barrier layer over the dielectric and a second capacitor electrode

comprising a top interconnect metal segment, wherein the bottom interconnect metal segment, the first barrier layer, the seed layer, the dielectric, the second layer and the top interconnect metal segment are fabricated in a single tool.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

## Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Nguyen T Ha whose telephone number is 571-272-1974. The examiner can normally be reached on Monday-Friday from 8:30AM to 6:00PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Dean Reichard can be reached on 571-272-2800 ext. 31. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should

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you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Nguyen T. Ha September 20, 2004

DEAN A. REICHARD
SUPERVISORY PATENT EXAMINER
TECHNOLOGY CENTER 2800